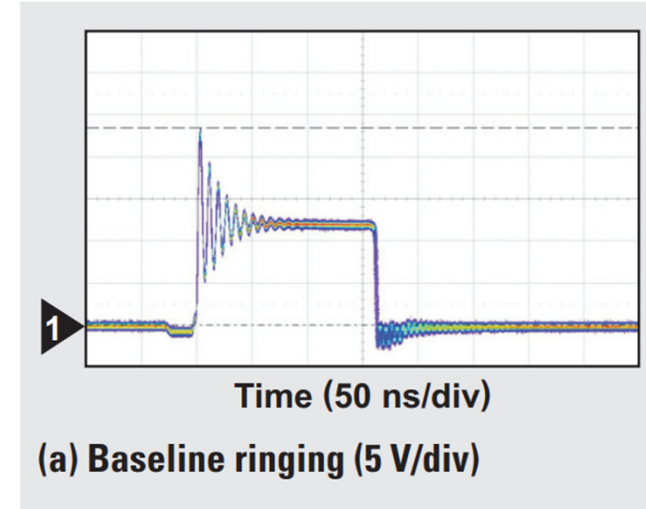
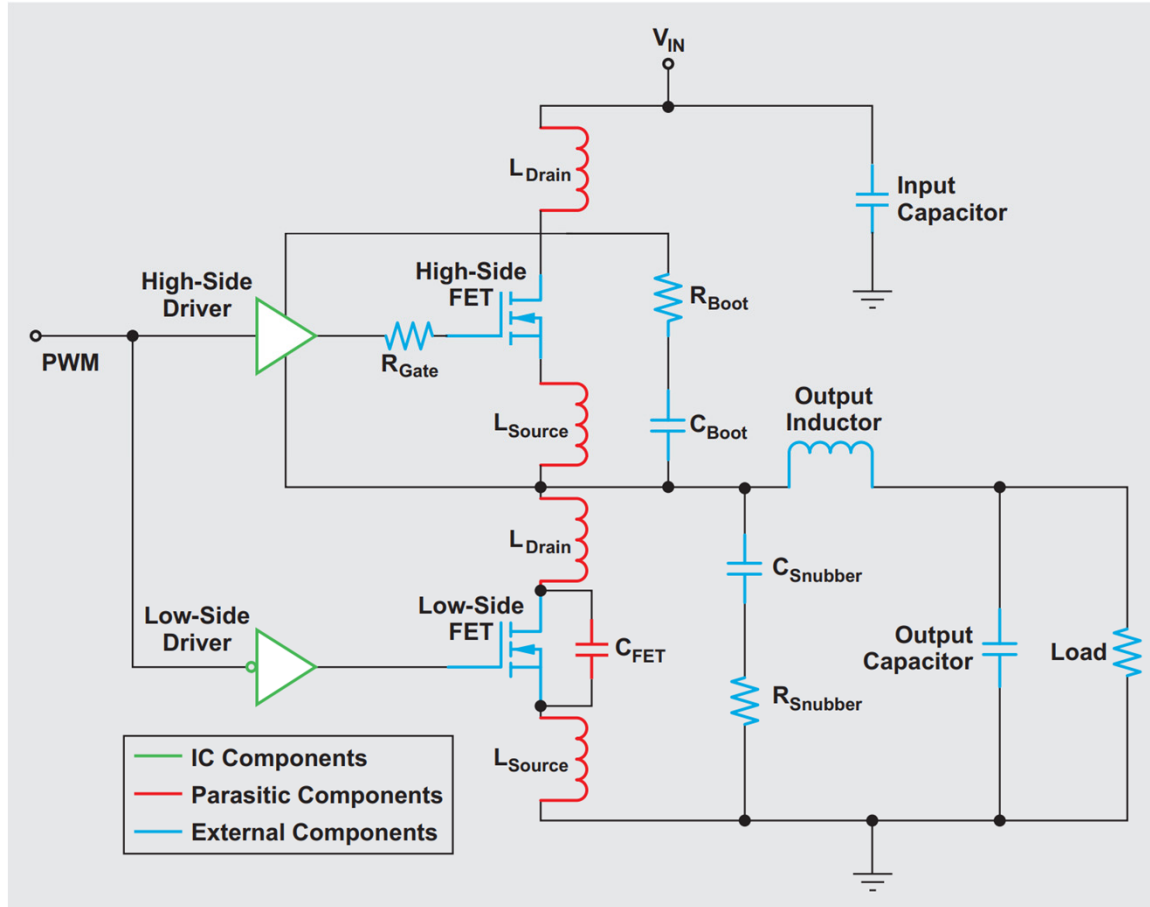
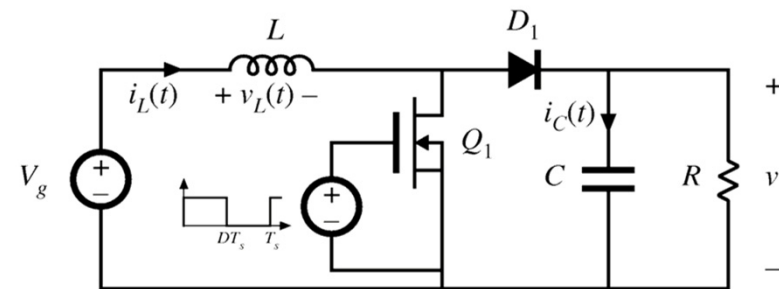
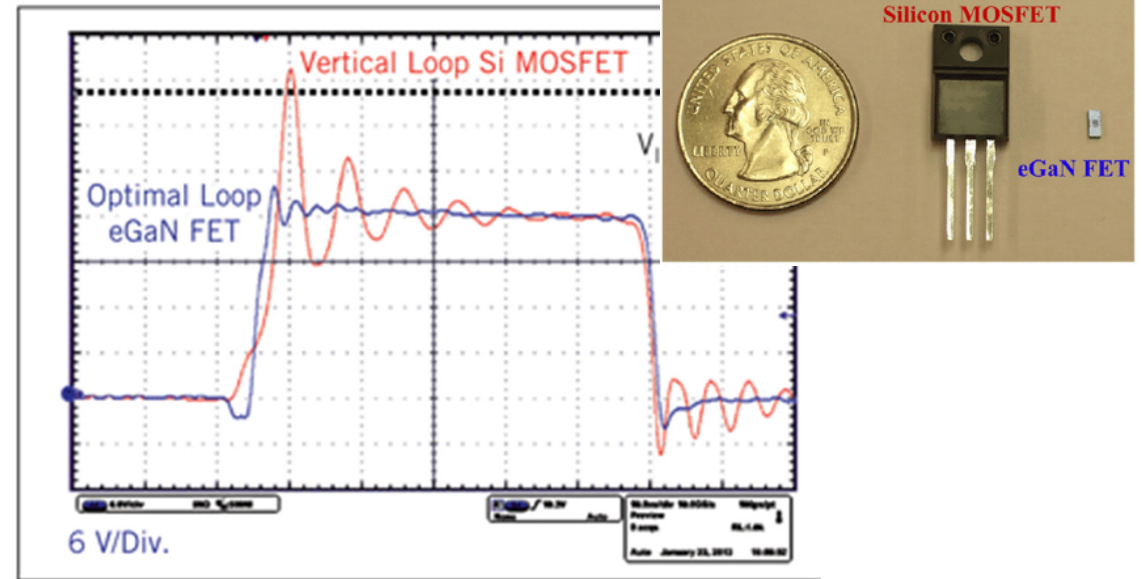
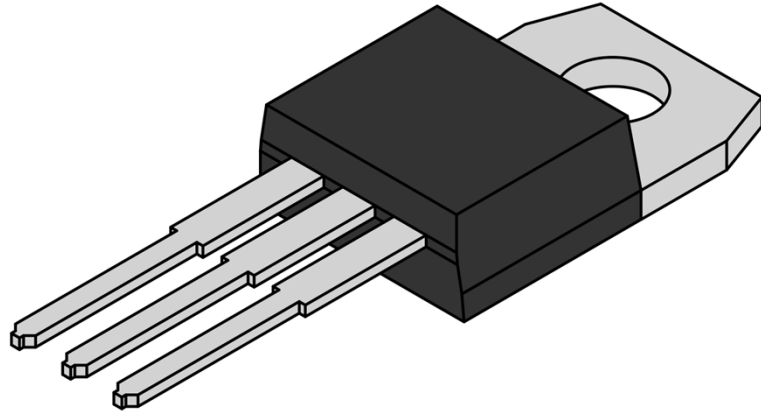


# Experimental Switching Waveforms



# Device Packaging and Layout



# The Double Pulse Test

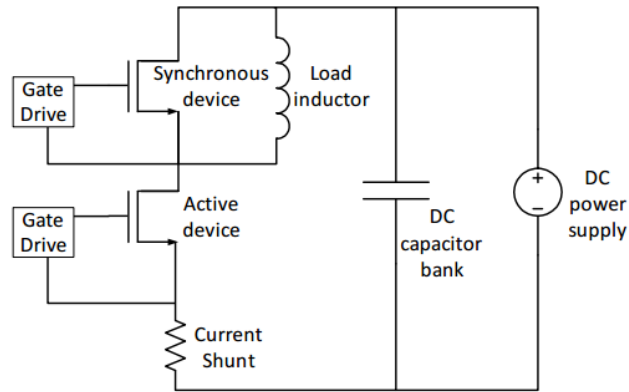


Fig. 7. Double pulse test circuit schematic.

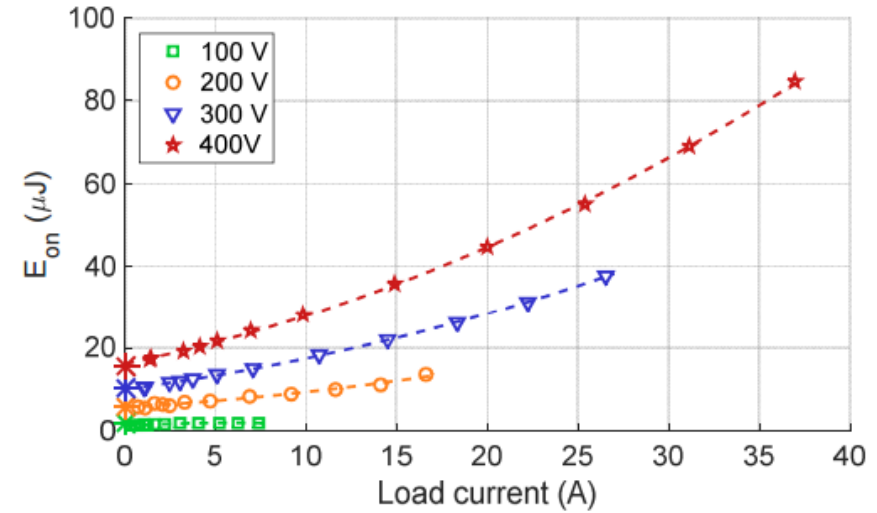
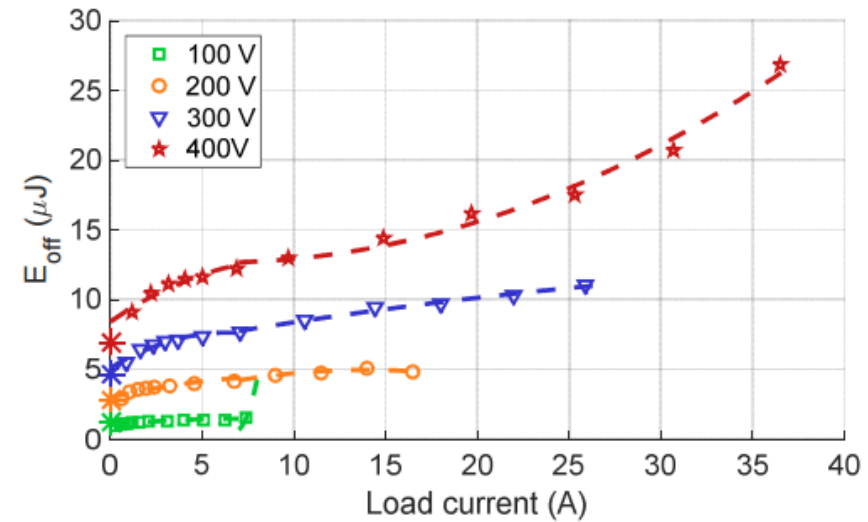
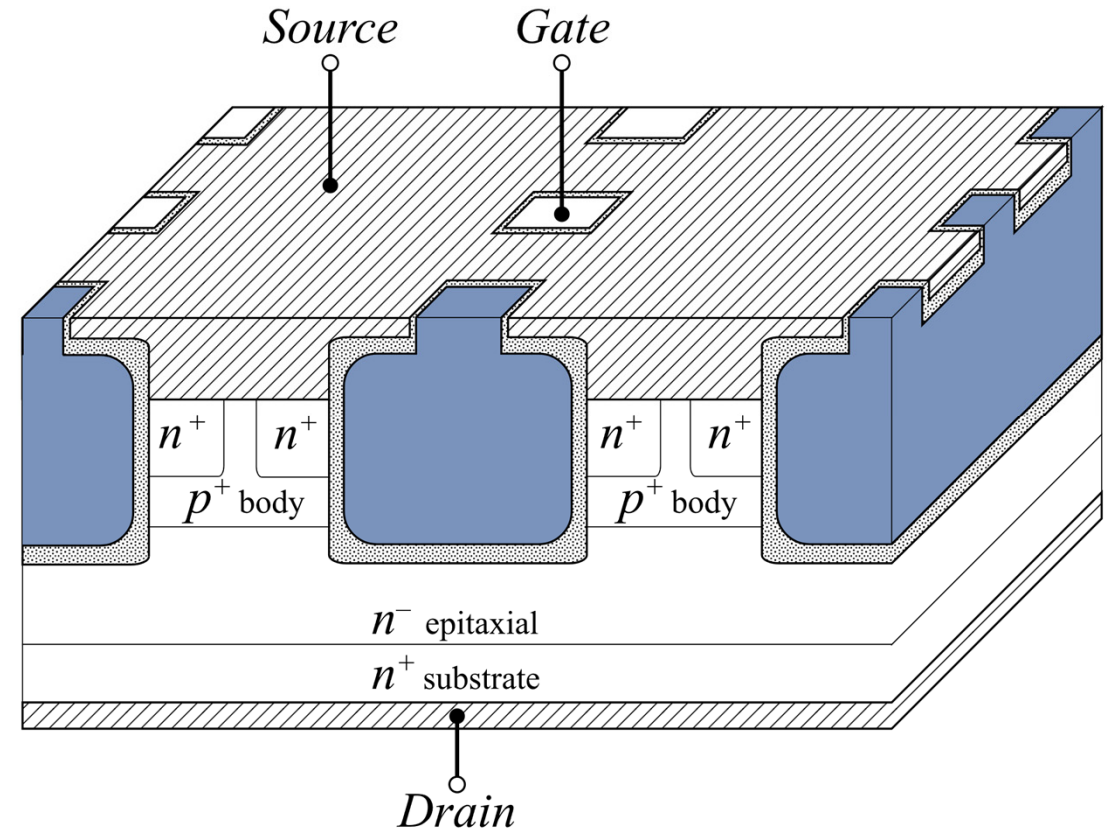
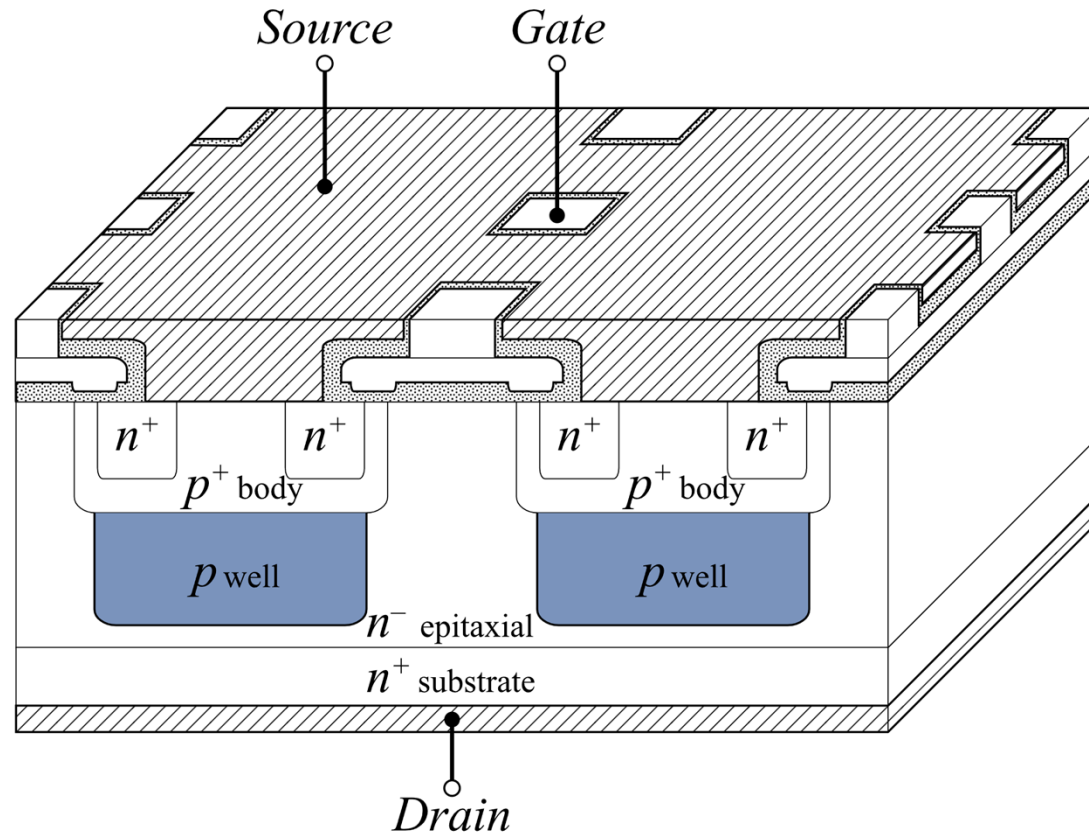


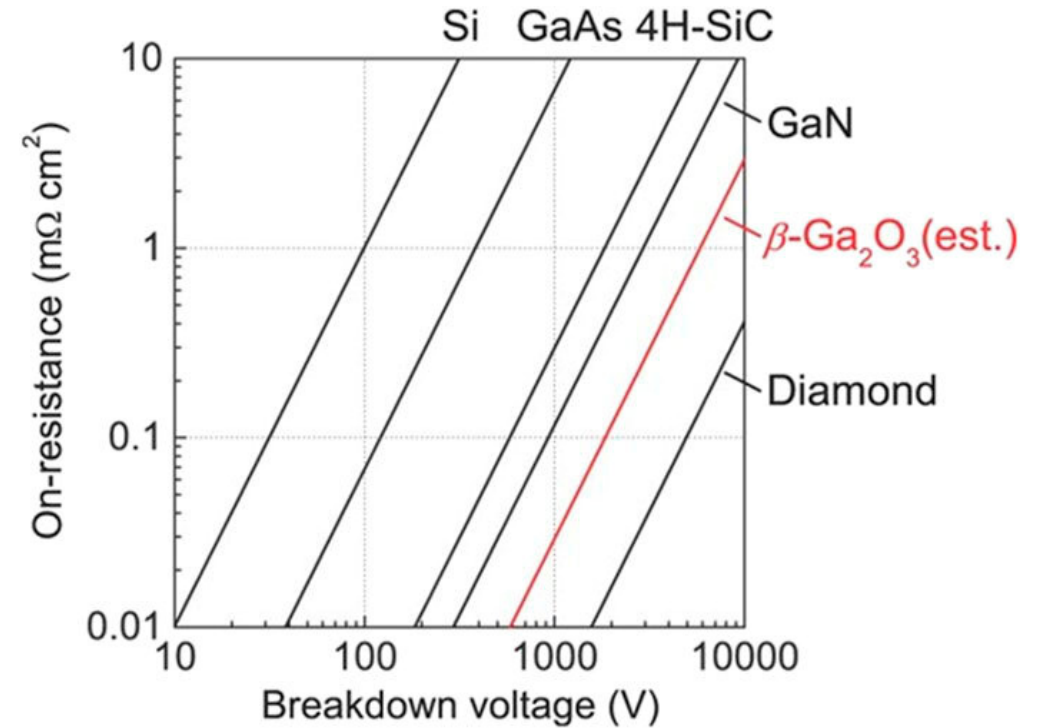
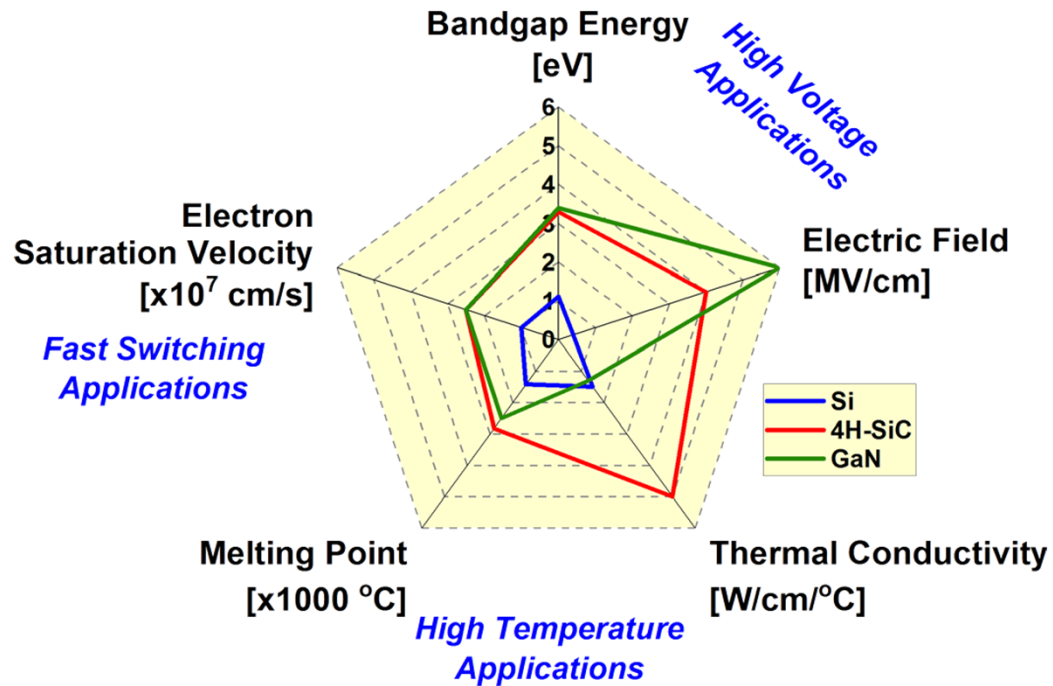
Fig. 16. Turn-on energy  $E_{on}$  at 25 °C.



# Other Device Structures

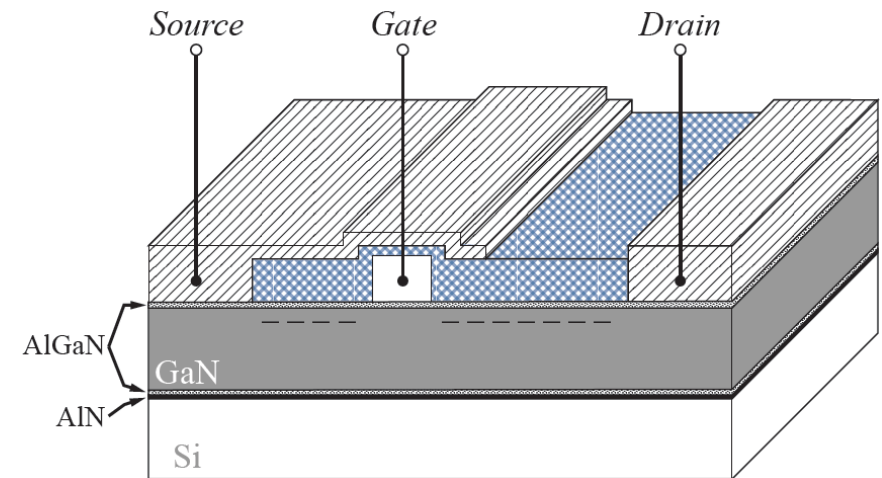
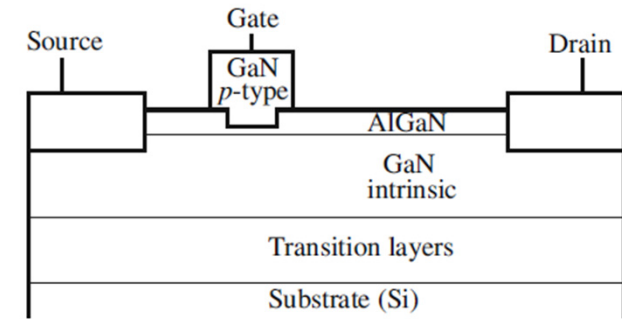


# Wide Bandgap Materials



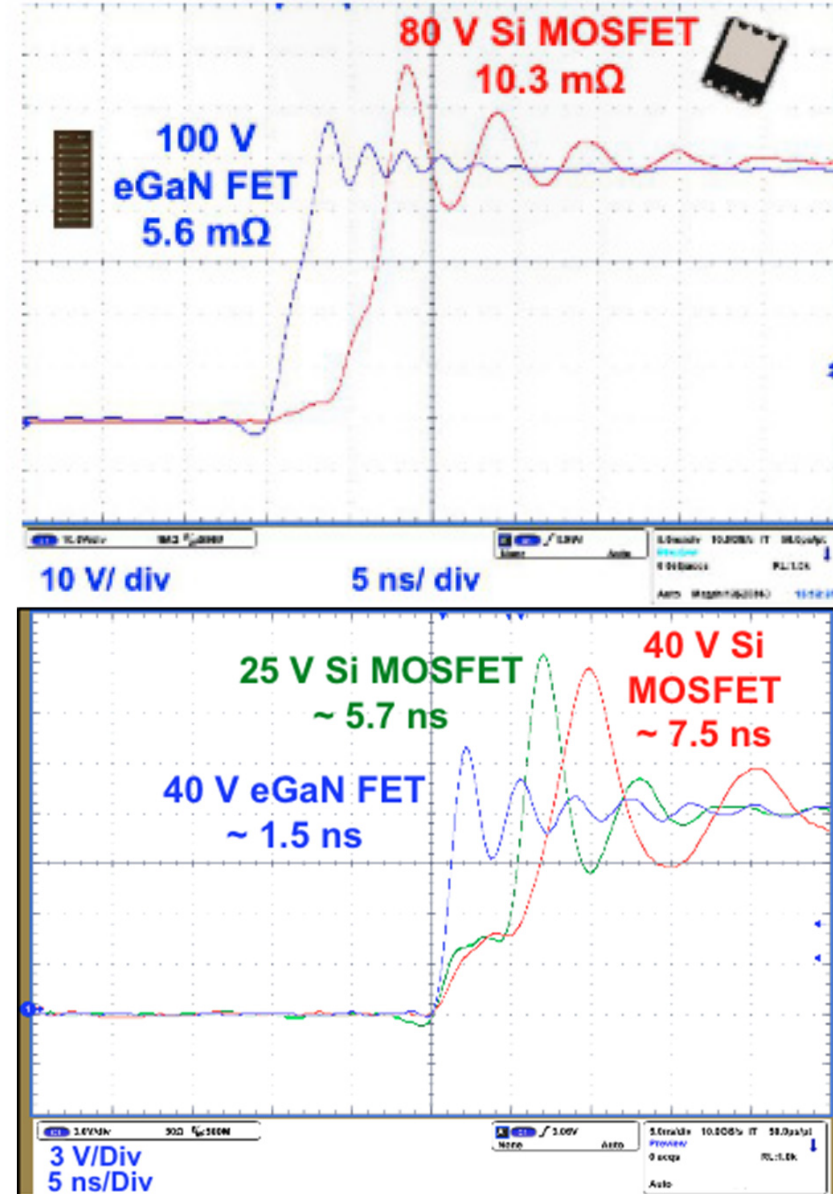
<https://potential.eecs.utk.edu/About.php?topic=PowerSemiconductors>

# GaN HEMTs



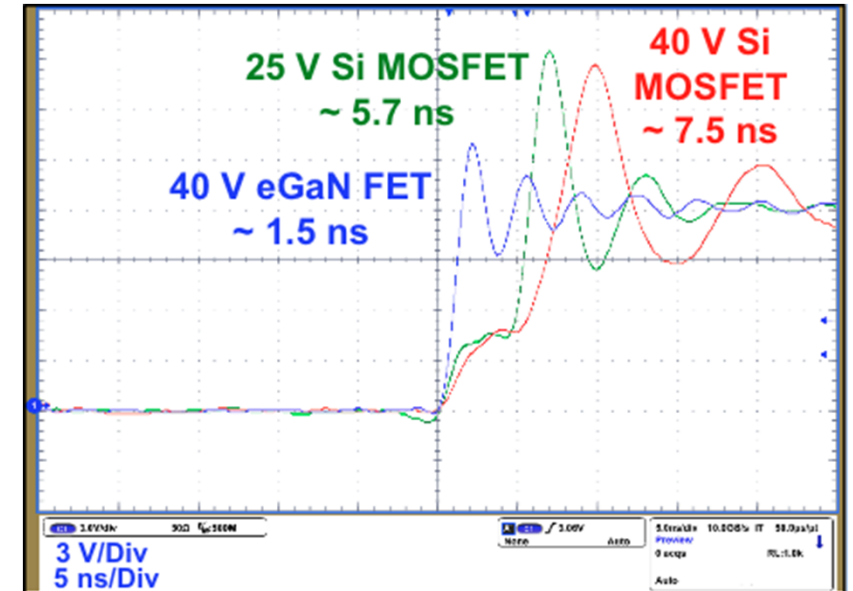
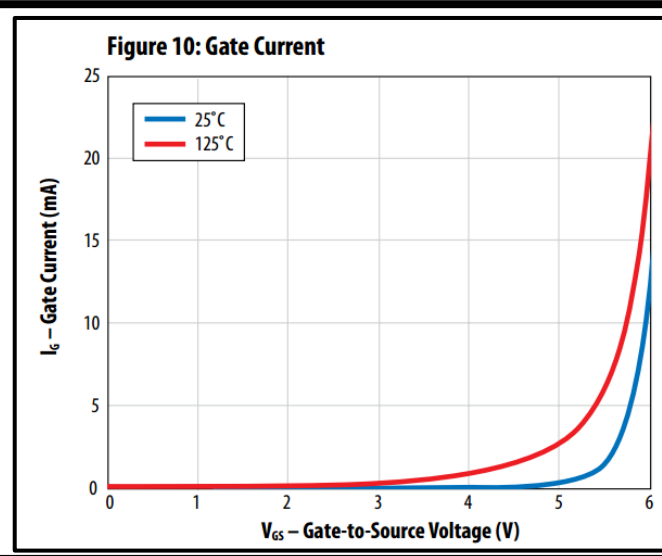
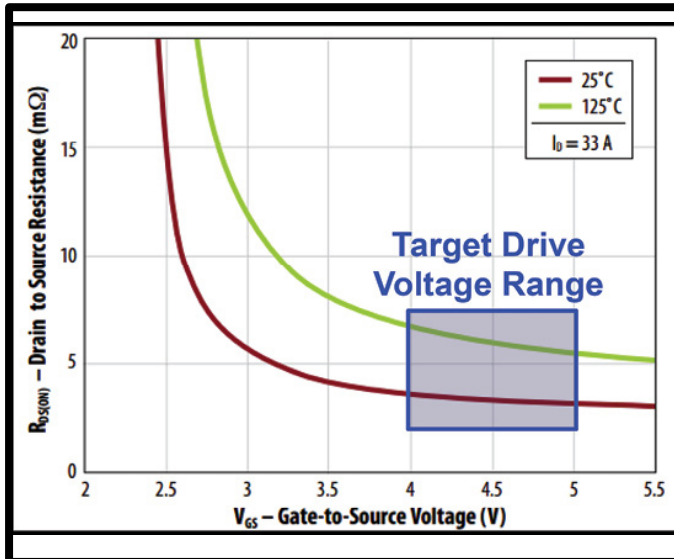
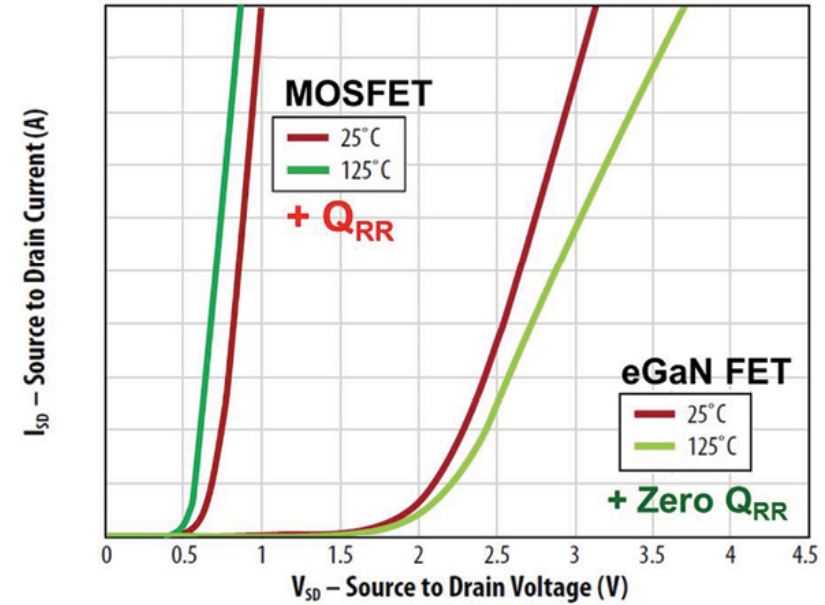
# Designing with GaN

- Because of high electric breakdown field and high electron velocity, GaN devices with comparable  $R_{on}$  can be significantly smaller and switch must faster.
- Need **very** good layout to prevent ringing from causing overvoltage and device failure.



# GaN Design Issues

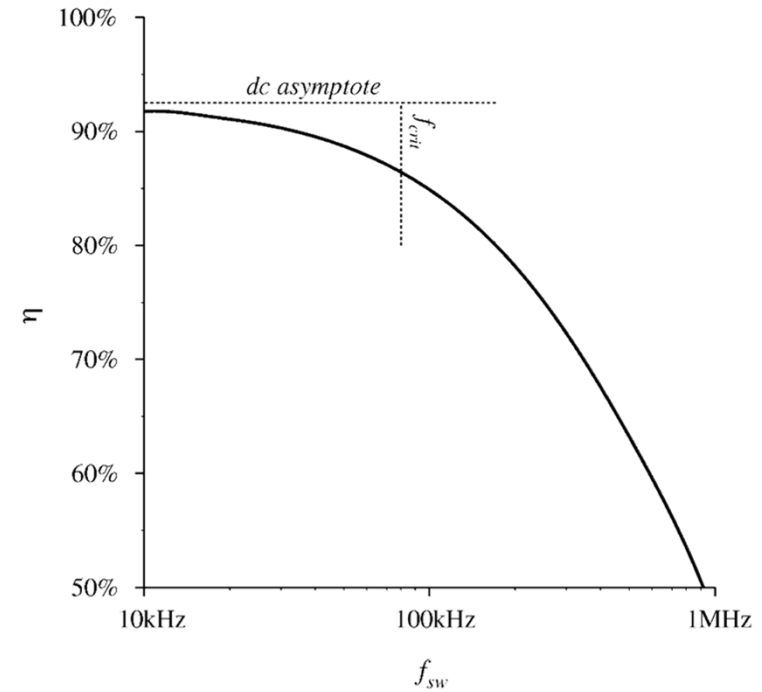
1. Reverse conduction mechanism
2. Sensitivity to parasitics
3. Gate robustness
4. Small size -> Thermal limitations



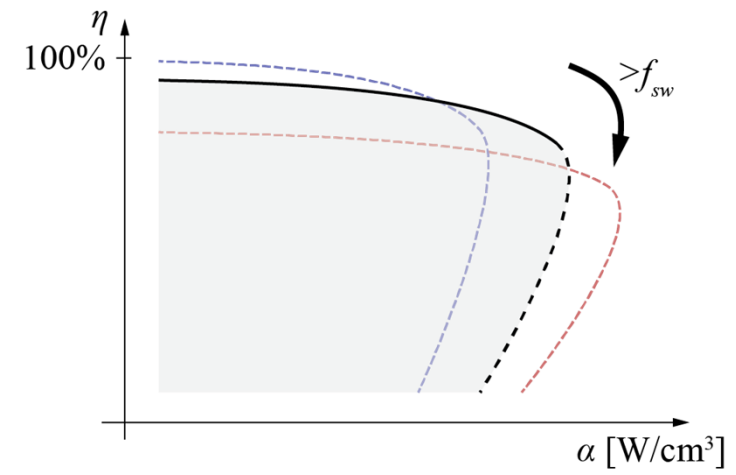


# Converter Efficiency Vs. $f_s$

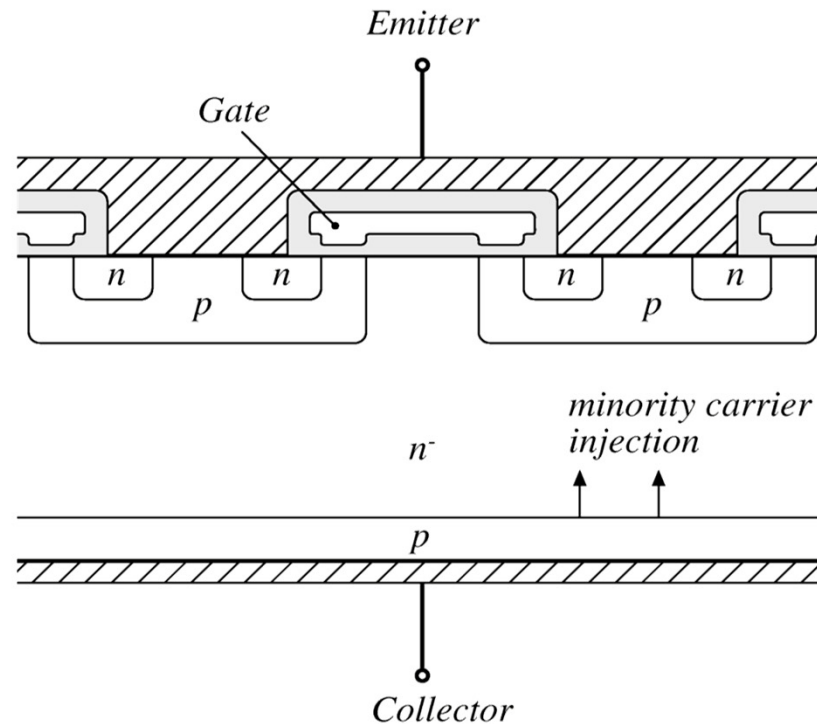
$$P_{loss} = P_{cond} + P_{fixed} + W_{tot} f_{sw}$$



# Converter Optimization

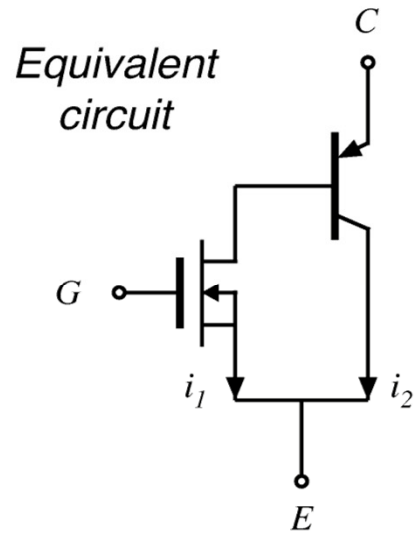
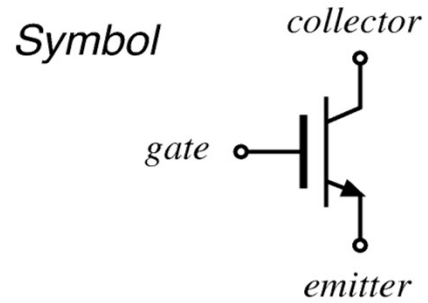


# Insulated Gate Bipolar Transistor



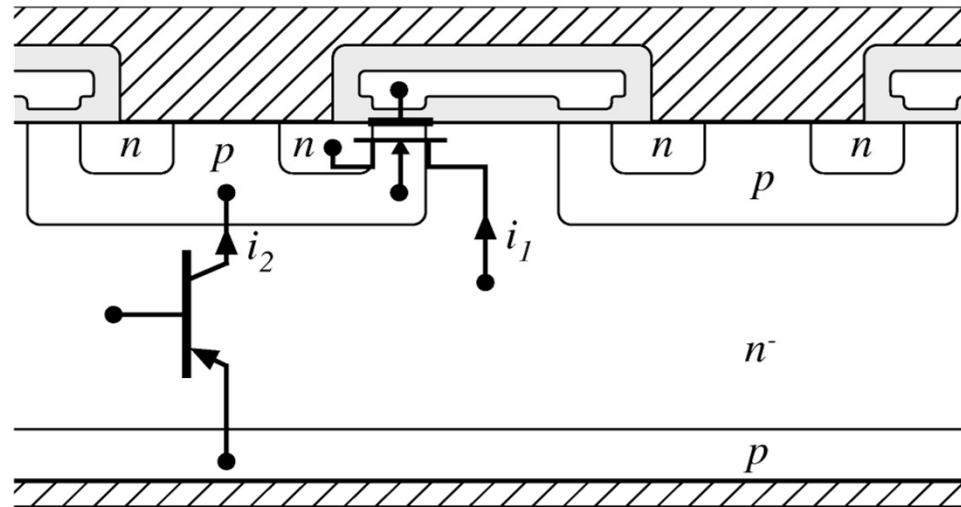
- A four-layer device
- Similar in construction to MOSFET, except extra  $p$  region
- On-state: minority carriers are injected into  $n$  region, leading to conductivity modulation
- compared with MOSFET: slower switching times, lower on-resistance, useful at higher voltages (up to 1700V)

# The IGBT



Fundamentals of Power Electronics

Location of equivalent devices



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Chapter 4: Switch realization

# IGBT: Current Tailing

